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Advances in Metrology for X-Ray and EUV Optics IV

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Contents

vii *Conference Committee*

SESSION 1 MEASUREMENTS

8501 02 **Review of substrate materials, surface metrologies and polishing techniques for current and future-generation EUV/x-ray optics (Invited Paper)** [8501-1]
R. Soufli, S. L. Baker, Lawrence Livermore National Lab. (United States); E. M. Gullikson, Lawrence Berkeley National Lab. (United States); T. McCarville, J. C. Robinson, Lawrence Livermore National Lab. (United States); D. Martínez-Galarce, Lockheed Martin Advanced Technology Ctr. (United States); M. Fernández-Perea, M. J. Pivovaroff, Lawrence Livermore National Lab. (United States)

8501 03 **Development of surface profile measurement method for ellipsoidal x-ray mirrors using phase retrieval** [8501-2]
T. Saitou, Y. Takei, H. Mimura, The Univ. of Tokyo (Japan)

8501 04 **Measurement of groove density variation of varied-line-space grating for high-resolution soft x-ray monochromator** [8501-3]
Y. Senba, H. Kishimoto, T. Miura, H. Ohashi, S. Goto, Japan Synchrotron Radiation Research Institute (Japan); T. Ishikawa, RIKEN (Japan)

8501 05 **Cross comparison of surface slope and height optical metrology with a super-polished plane Si mirror** [8501-4]
N. A. Artemiev, D. J. Merthe, Lawrence Berkeley National Lab. (United States); D. Cocco, N. Kelez, SLAC National Accelerator Lab. (United States); T. J. McCarville, M. J. Pivovaroff, Lawrence Livermore National Lab. (United States); D. W. Rich, J. L. Turner, SLAC National Accelerator Lab. (United States); W. R. McKinney, V. V. Yashchuk, Lawrence Berkeley National Lab. (United States)

8501 06 **Using MountainsMap (Digital Surf) surface analysis software as an analysis tool for x-ray mirror optical metrology data** [8501-5]
A. Duffy, B. Yates, Canadian Light Source Inc. (Canada); P. Takacs, Brookhaven National Lab. (United States)

SESSION 2 BENDERS

8501 07 **Optimal setting of bendable optics based on FEA calculations** [8501-6]
N. A. Artemiev, K. P. Chow, Lawrence Berkeley National Lab. (United States); D. La Civita, European XFEL GmbH (Germany); D. J. Merthe, Y.-D. Chuang, W. R. McKinney, V. V. Yashchuk, Lawrence Berkeley National Lab. (United States)

8501 08 **Methodology for optimal in situ alignment and setting of bendable optics for diffraction-limited focusing of soft x-rays** [8501-7]
D. J. Merthe, V. V. Yashchuk, K. A. Goldberg, M. Kunz, N. Tamura, W. R. McKinney, N. A. Artemiev, R. S. Celestre, G. Y. Morrison, E. Anderson, B. V. Smith, E. E. Domning, S. B. Rekawa, H. A. Padmore, Lawrence Berkeley National Lab. (United States)

8501 09 **Ex situ tuning of bendable x-ray mirrors for optimal beamline performance** [8501-8]
W. R. McKinney, V. V. Yashchuk, D. J. Merthe, N. A. Artemiev, K. Goldberg, Lawrence Berkeley National Lab. (United States)

SESSION 3 PROFILERS

8501 0A **Development of a high-speed nanoprofiler using normal vector tracing** [8501-9]
T. Kitayama, H. Matsumura, K. Usuki, T. Kojima, J. Uchikoshi, Osaka Univ. (Japan); Y. Higashi, High Energy Accelerator Research Organization (Japan); K. Endo, Osaka Univ. (Japan)

8501 0B **Progress of multi-beam long trace-profiler development** [8501-10]
M. V. Gubarev, NASA Marshall Space Flight Ctr. (United States); D. J. Merthe, Lawrence Berkeley National Lab. (United States); K. Kilaru, T. Kester, R. Eng, B. Ramsey, NASA Marshall Space Flight Ctr. (United States); W. R. McKinney, Lawrence Berkeley National Lab. (United States); P. Z. Takacs, Brookhaven National Lab. (United States); V. V. Yashchuk, Lawrence Berkeley National Lab. (United States)

8501 0D **Dynamic surface roughness profiler** [8501-12]
B. Kimbrough, N. Brock, J. Millerd, 4D Technology Corp. (United States)

SESSION 4 SCATTER

8501 0F **Roughness characterization of EUV multilayer coatings and ultra-smooth surfaces by light scattering** [8501-14]
M. Trost, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany) and Friedrich-Schiller-Univ. Jena (Germany); S. Schröder, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany); C. C. Lin, SEMATECH North (United States); A. Duparré, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany); A. Tünnermann, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany) and Friedrich-Schiller-Univ. Jena (Germany)

8501 0G **Improved thermal stability of Mg/Co multilayer by introducing Zr barrier layer** [8501-15]
H. Li, S. Zhou, X. Wang, J. Zhu, Z. Wang, Tongji Univ. (China)

SESSION 5 CALIBRATION AND MULTILAYERS METROLOGY

8501 0I **Microroughness measurements and EUV calibration of the solar ultraviolet imager multilayer-coated mirrors** [8501-17]
D. Martínez-Galarce, Lockheed Martin Advanced Technology Ctr. (United States); R. Soufli, Lawrence Livermore National Lab. (United States); D. L. Windt, Reflective X-Ray Optics LLC (United States); M. Bruner, Bermar Science & Technology LLC (United States); E. Gullikson, Lawrence Berkeley National Lab. (United States); S. Khatri, L-3 Communications Tinsley Labs. Inc. (United States); E. Spiller, J. Robinson, S. Baker, Lawrence Livermore National Lab. (United States); E. Prast, Research Electro-Optics, Inc. (United States)

8501 0J **Development of grating-based hard x-ray Talbot interferometry for optics and beam wavefront characterization at the advanced photon source** [8501-18]
S. Marathe, M. J. Wojcik, N. G. Kujala, A. T. Macrander, Argonne National Lab. (United States); H. H. Wen, National Institutes of Health (United States); C. Liu, K. Fezzaa, R. Divan, D. C. Mancini, L. Assoufid, Argonne National Lab. (United States)

Author Index

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